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APPLICATION NO.	FIL	ING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/765,931	10/765,931 01/29/2004		Youichi Kukimoto	Q79041	1863
23373	7590	08/09/2006	EXAMINER		
SUGHRUE	•		NGUYEN, KHIEM D		
2100 PENN SUITE 800	SYLVANIA	A AVENUE, N.W.		ART UNIT	PAPER NUMBER
WASHING	TON, DC	20037	2823		
				DATE MAILED: 08/09/200	06

Please find below and/or attached an Office communication concerning this application or proceeding.

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•		1	•	
Office Action Summary	10/765,931	KUKIMOTO ET AI	L.	_
omoc Aodon Gammary	Examiner	Art Unit		
The MAN INC DATE of the comment of t	Khiem D. Nguyen	2823		
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the (orrespondence ad	Idress	
A SHORTENED STATUTORY PERIOD FOR REPLY WHICHEVER IS LONGER, FROM THE MAILING DA - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If NO period for reply is specified above, the maximum statutory period v - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION 36(a). In no event, however, may a reply be tire will apply and will expire SIX (6) MONTHS from a cause the application to become ABANDONE	N. nely filed the mailing date of this co	·	
Status				
1)⊠ Responsive to communication(s) filed on <u>05 Ju</u>	una 2006			
	action is non-final.			
3) Since this application is in condition for allowar		osecution as to the	e merits is	
closed in accordance with the practice under E	· ·			
Disposition of Claims				
4)⊠ Claim(s) <u>2-4 and 8-12</u> is/are pending in the app	alication			
4a) Of the above claim(s) is/are withdraw				
5) Claim(s) is/are allowed.	William Consideration.			
6)⊠ Claim(s) <u>2-4 and 8-12</u> is/are rejected.				
7) Claim(s) is/are objected to.				
8) Claim(s) are subject to restriction and/or	r election requirement.			
Application Papers				
9) The specification is objected to by the Examine	r			
10)⊠ The drawing(s) filed on 29 January 2004 is/are:		I to by the Examin	er	
Applicant may not request that any objection to the				
Replacement drawing sheet(s) including the correct			FR 1.121(d).	
11) The oath or declaration is objected to by the Ex		_		
Priority under 35 U.S.C. § 119				
12)⊠ Acknowledgment is made of a claim for foreign	priority under 35 U.S.C. § 119(a)-(d) or (f).		
a)⊠ All b)□ Some * c)□ None of:				
1. Certified copies of the priority documents				
2. Certified copies of the priority documents	• •	***	•	
3. Copies of the certified copies of the prior	•	ed in this National	Stage	
application from the International Bureau		. d		
* See the attached detailed Office action for a list	or the certified copies not receive	a.		
Attachment(s)				
1) X Notice of References Cited (PTO-892)	4) Interview Summary			
2) Notice of Draftsperson's Patent Drawing Review (PTO-948)	Paper No(s)/Mail D 5) Notice of Informal F		∩_152)	
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 06/05/06; 06/15/06.	6) Other:	atent Application (P10	J-10 6]	

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DETAILED ACTION

Continued Examination Under 37 CFR 1.114

A request for continued examination under 37 CFR 1.114, including the fee set forth in 37 CFR 1.17(e), was filed in this application after final rejection. Since this application is eligible for continued examination under 37 CFR 1.114, and the fee set forth in 37 CFR 1.17(e) has been timely paid, the finality of the previous Office action has been withdrawn pursuant to 37 CFR 1.114. Applicant's submission filed on has been entered. A new rejection is made as set forth in this Office Action. Claims (2-4 and 8-12) are pending in the application.

Information Disclosure Statement

2. The Information Disclosure Statement filed on June 05th, 2006 and June 15th, 2006 has been considered.

Response to Applicants' Amendment

3. The Declaration under 37 CFR 1.132 filed June 05th, 2006 is sufficient to overcome the rejection of claims 5-6 and 8-9 based upon Ikeda et al. (U.S. Patent 6,923,875).

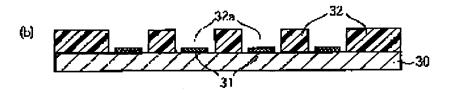
Claim Rejections - 35 USC § 103

- 4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

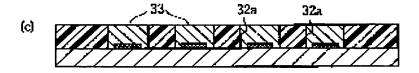
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5. Claims 2-4 and 8-12 are rejected under 35 U.S.C. 103(a) as being unpatentable over Sakuyama Seiki ("Method for forming bump", Japan Publication number 2002-334895, English translation) in view of Amita et al. (U.S. Pub. 2002/0046627).

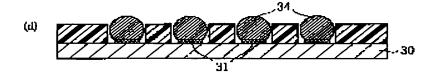
In re claim 8, <u>Sakuyama</u> discloses a solder deposition method comprising the steps of: forming a dam 32 around an electrodes 31 on a substrate 30 (Detailed Description, pages 1-2, paragraph [0006] and FIG. 3b);



applying a solder precipitating composition 33 to the substrate 30 (FIG. 3c); and



depositing solder 34 on the surface of the electrode 31while heating the solder precipitating composition 33 applied (Detailed Description, page 2, paragraph [0006] and FIG. 3d).



<u>Sakuyama</u> discloses that the solder precipitating composition 33 comprises a pewter paste 33 (Detailed Description, page 2, paragraph [0009] but does not explicitly discloses or suggest wherein the solder precipitating composition comprises a tin powder, and a complex of at least one member selected from the group consisting of silver ions

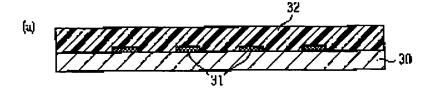
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and copper ions, and at least one member selected from the group consisting of aryl phosphines, alkyl phosphines and azoles.

Amita, however, disclose a solder deposition method comprise the steps of applying a solder precipitating composition 10 to the substrate 12 wherein the solder precipitating composition comprises a tin powder, and a complex of at least one member selected from the group consisting of silver ions (Sn-Ag) and copper ions (Sn-Cu), (page 4, paragraph [0063] and FIG. 3) and at least one member selected from the group consisting of azoles (benzotriazole) (page 8, paragraph [0115]).

Therefore, it would have been obvious to one of ordinary skill in the art at the time of the invention was made to combine the teaching of Sakuyama and Amita to enable the process of applying a solder precipitating composition comprises a tin powder, and a complex selected from silver ions and azoles of Sakuyama to be performed and furthermore to obtain a solder powder which have excellent storage stability and ensure excellent properties in and after reflow (page 1, paragraph [0003], Amita) and also prevent the circuit copper from rusting (page 8, paragraph [0115], Amita).

In re claim 2, as applied to claim 8 above, Sakuyama in combination with Amita discloses all claimed limitations including the limitation wherein forming a dam includes the steps of: forming a resin film 32 on the surface of the substrate 30 (FIG. 3a); and



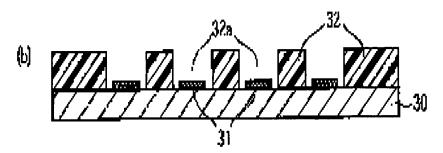
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providing an opening part 32a in the resin film 32 so that a dam is formed around an electrode 31 on a substrate 30 (pages 1-2, paragraph [0006], Sakuyama).

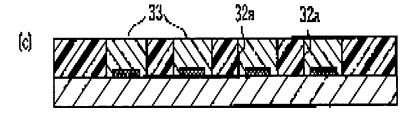
In re claim 3, as applied to claim 8 above, Sakuyama in combination with Amita discloses all claimed limitations including the limitation wherein the dam 32 is not removed after depositing solder 34 (FIG. 3d, Sakuyama).

In re claim 4, as applied to claim 8 above, Sakuyama in combination with Amita discloses all claimed limitations including the limitation wherein the substrate is a via-on-pad structured substrate (pages 1-2, paragraph [0006] and FIGS. 3(a)-(e), Sakuyama).

In re claim 9, <u>Sakuyama</u> discloses a solder deposition method comprising the steps of: forming a dam 32 around an electrodes 31 on a substrate 30 (Detailed Description, pages 1-2, paragraph [0006] and FIG. 3b);

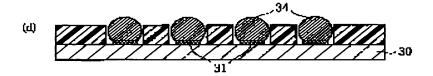


applying a solder precipitating composition 33 to the substrate 30 (FIG. 3c); and



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depositing solder 34 on the surface of the electrode 31while heating the solder precipitating composition 33 applied (Detailed Description, page 2, paragraph [0006] and FIG. 3d).



<u>Sakuyama</u> discloses that the solder precipitating composition 33 comprises a pewter paste 33 (Detailed Description, page 2, paragraph [0009] but does not explicitly discloses or suggest wherein the solder precipitating composition comprises a tin powder, and a salt of at least one metal selected from the group consisting of lead, copper and silver.

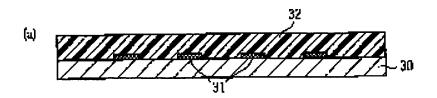
Amita, however, disclose a solder deposition method comprise the steps of applying a solder precipitating composition 10 to the substrate 12 wherein the solder precipitating composition comprises a tin powder, and a salt of at least one metal selected from the group consisting of lead (Sn-Pb), copper (Sn-Cu) and silver (Sn-Ag) (page 8, paragraph [0115]).

Therefore, it would have been obvious to one of ordinary skill in the art at the time of the invention was made to combine the teaching of Sakuyama and Amita to enable the process of applying a solder precipitating composition comprises a tin powder, and a salt of at least one metal selected from the group consisting of lead, copper and silver of Sakuyama to be performed and furthermore to obtain a solder powder which have excellent storage stability and ensure excellent properties in and after reflow (page

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1, paragraph [0003], Amita) and also prevent the circuit copper from rusting (page 8, paragraph [0115], Amita).

In re claim 10, as applied to claim 9 above, Sakuyama in combination with Amita discloses all claimed limitations including the limitation wherein forming a dam includes the steps of: forming a resin film 32 on the surface of the substrate 30 (FIG. 3a); and



providing an opening part 32a in the resin film 32 so that a dam is formed around an electrode 31 on a substrate 30 (pages 1-2, paragraph [0006], Sakuyama).

In re claim 11, as applied to claim 9 above, Sakuyama in combination with Amita discloses all claimed limitations including the limitation wherein the dam 32 is not removed after depositing solder 34 (FIG. 3d, Sakuyama).

In re claim 12, as applied to claim 9 above, Sakuyama in combination with Amita discloses all claimed limitations including the limitation wherein the substrate is a via-on-pad structured substrate (pages 1-2, paragraph [0006] and FIGS. 3(a)-(e), Sakuyama).

Response to Applicants' Amendment and Arguments

6. Applicant's arguments, see Amendment under 37 C.F.R § 1.114, filed June 05th, 2006 on page 6, with respect to the rejection(s) of claim(s) 1-9 under 35 U.S.C. 103(a) have been fully considered and are persuasive. Therefore, the rejection in paper No. 020306 mailed on February 7th, 2006 has been withdrawn. However, upon further consideration, a new ground(s) of rejection is made in view of the newly discovered reference to Amita et al.

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(U.S. Pub. 2002/0046627) applied under 35 U.S.C. 103(a) rejection as described above in

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Paragraph 5 presented in this Office Action.

Conclusion

7. Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Khiem D. Nguyen whose telephone number is (571) 272-

1865. The examiner can normally be reached on Monday-Friday (8:30 AM - 5:30 PM).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Matthew S. Smith can be reached on (571) 272-1907. The fax phone number

for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the

Patent Application Information Retrieval (PAIR) system. Status information for

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Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO

Customer Service Representative or access to the automated information system, call

800-786-9199 (IN USA OR CANADA) or 571-272-1000.

K.N.

August 03, 2006

MATTHEW SMITH
SUPERVISORY PATENT EXAMINER

Ma O J'Sus

TECHNOLOGY CENTER 2800